

ABSTRACT OF THE DISCLOSURE

A substrate processing apparatus of the present invention is surrounded by a hermetic member, and the internal space thereof is divided by a hermetic member into a rinse and dry processing chamber, a first and second liquid chemical processing chambers, and a substrate transport chamber. Openings for allowing transportation of substrates to and from corresponding chambers are capable of being exposed and blocked by open/close mechanisms including sealing means. Hence, substrates being processed can be transported in an environment isolated from outside an external atmosphere containing oxygen, to thereby suppress formation of unnecessary oxide films or generation of water marks on the surfaces of substrates while being transported. Further, exhaust emission can be reduced, which emission serves to prevent diffusion of an atmosphere containing vapor of a liquid chemical to the outside of the substrate processing apparatus.